

Fig. 1. SnO film deposited on a 200mm silicon wafer using the precursor provided by Pegasus Chemicals and water vapour at 150°C.

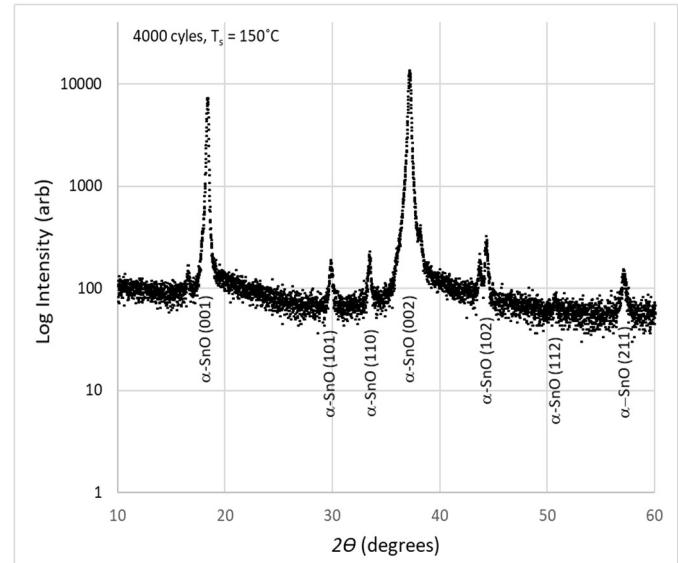


Fig. 2. X-ray diffraction patterns of an SnO film deposited at 150°C exhibiting preferred <001> textured growth.

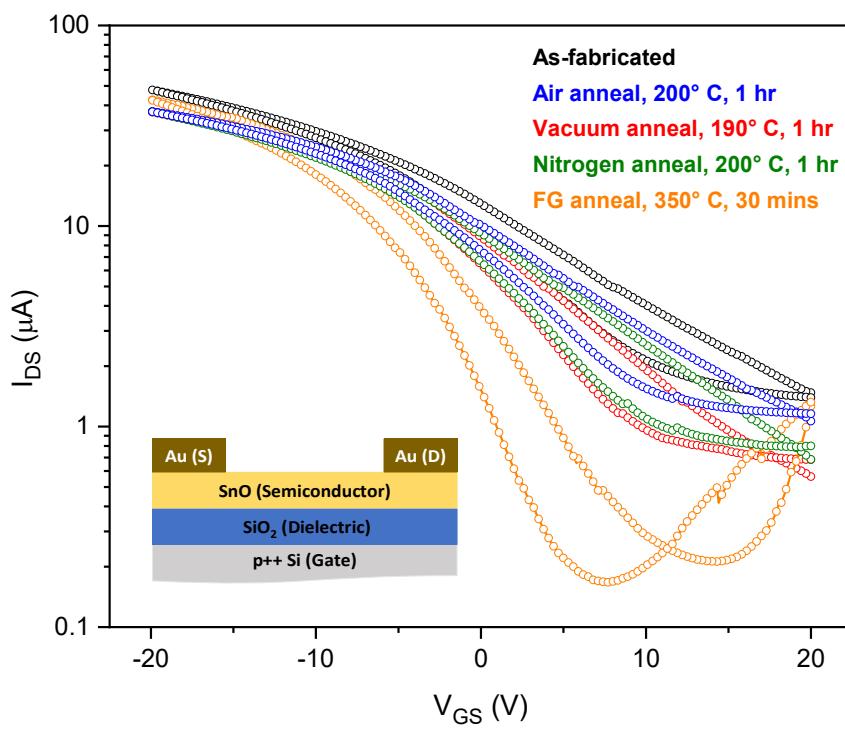


Fig. 3. SnO TFT characteristics, as-fabricated and after various post-fabrication heat treatments.